Sheet 1 of 1 **Docket Number (Optional) Application Number** Form PTO-1449 N tY tAssigned 3579.2US (98-0062.02/US) INFORMATION DISCLOSURE CITATION 10/729/12 Applicant Dapeng Wang IN AN APPLICATION (Use several sheets if necessary) Filing Date December 5, 2003 Group Art Unit Unknown **U.S. PATENT DOCUMENTS** EXAMINER INITIAL DOCUMENT NUMBER FILING DATE IF APPROPRIATE DATE NAME CLASS SUBCLASS 5,232,875 08/1993 Tuttle et al. 5,514,245 05/1996 Doan et al. 5,624,299 04/1997 Shendon 5,664,989 09/1997 Nakata et al. 5,692,947 12/1997 Talieh et al. 5,692,950 12/1997 Rutherford et al. FOREIGN PATENT DOCUMENTS DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS YES NO 米 57023965-A 02/1982 JP × 58045861 A 03/1983 JP **OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.) Wang et al., Von Mises Stress in Chemical-Mechanical Polishing Processes, J. Electrochem. Soc., Vol. 144, No. 3, March 1997 pp. 1121-27.

EXAMINER: Initial if citation consid red, wheth r or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not consid red. Includ copy f this form with next communication t the applicant.

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